

5657. (New) The method as recited in claim 49, further comprising the step of etching a plurality of pyramid-shaped depressions into the silicon substrate in the first subsections.--.

REMARKS

With the cancellation herein, without prejudice, of claims 20 to 38, and the addition of new claims 39 to 57, claims 39 to 57 are pending in the present application.

Applicants assert that the subject matter of the present application is new, non-obvious and useful. Prompt consideration and allowance of the application is respectfully requested.

Respectfully submitted,

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